

Interview Summary

Application No.

10/735,769

Applicant(s)

KAWAMURA ET AL.

Examiner

Daborah Chacko-Davis

Art Unit

1756

All participants (applicant, applicant's representative, PTO personnel):

(1) Ms. Jennifer M. Hayes, Reg. No. 40,641.

(3) Daborah Chacko-Davis.

(2) Ms. Nyeemah Grazier.

(4) _____.

Date of Interview: 26 July 2007.

Type: a) ☐ Telephonic b) ☐ Video Conference
c) ☒ Personal [copy given to: 1) ☐ applicant 2) ☒ applicant's representative]

Exhibit shown or demonstration conducted: d) ☒ Yes e) ☐ No.

If Yes, brief description: An Illustration of the difference between the substrate and initiating layer of Kawamura et al., and that of the applicant's claimed invention.

Claim(s) discussed: 1, and 14.

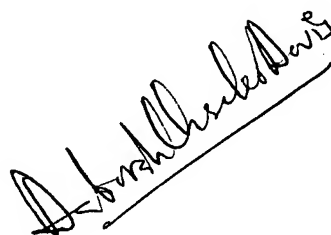
Identification of prior art discussed: U. S. Patent No. 6,919,158 (Kawamura et al).

Agreement with respect to the claims f) ☐ was reached. g) ☒ was not reached. h) ☐ N/A.

Substance of Interview including description of the general nature of what was agreed to if an agreement was reached, or any other comments: See Continuation Sheet.

(A fuller description, if necessary, and a copy of the amendments which the examiner agreed would render the claims allowable, if available, must be attached. Also, where no copy of the amendments that would render the claims allowable is available, a summary thereof must be attached.)

THE FORMAL WRITTEN REPLY TO THE LAST OFFICE ACTION MUST INCLUDE THE SUBSTANCE OF THE INTERVIEW. (See MPEP Section 713.04). If a reply to the last Office action has already been filed, APPLICANT IS GIVEN A NON-EXTENDABLE PERIOD OF THE LONGER OF ONE MONTH OR THIRTY DAYS FROM THIS INTERVIEW DATE, OR THE MAILING DATE OF THIS INTERVIEW SUMMARY FORM, WHICHEVER IS LATER, TO FILE A STATEMENT OF THE SUBSTANCE OF THE INTERVIEW. See Summary of Record of Interview requirements on reverse side or on attached sheet.



Examiner Note: You must sign this form unless it is an Attachment to a signed Office action.

Examiner's signature, if required

Continuation of Substance of Interview including description of the general nature of what was agreed to if an agreement was reached, or any other comments: It was discussed that the pattern forming method (in accordance to the illustration and the instant specification) involves the use of a substrate wherein the initiator is fixed throughout the whole area of the substrate and then image-wise exposed to light to inactivate the polymerization-initiating ability of the initiator in the exposed region alone which is different than that of the pattern formation of Kawamura i.e., Kawamura teaches that the exposed region initiates the species to activate polymerization activity.